

U.S. Department of Commerce, Patent and Trademark Office (PTO Form 449 modified)		Docket No. 7938/ETCH/SILICON	Serial No. 10/628,001
INFORMATION DISCLOSURE STATEMENT BY APPLICANT (Use several sheets if necessary)		Applicant Davis, et al.	Confirmation No.:
Examiner		Filing Date 07/25/03	Group

## U.S. Patent Documents

*Examiner Initial	Document Number	Issue Date	Applicant(s) Name	Class	Subclass	Filing Date If Appropriate
AS	A1	6,419,846	07/16/2002	Toprac et al.	216	60
AS	A2	6,521,080	02/18/2003	Balasubramhanya et al.	156	345.24
	A3					
	A4					
	A5					
	A6					
	A7					
	A8					
	A9					
	A10					

## Foreign Patent Documents

*Examiner Initial	Document Number	Date	Country	Class	Subclass	Translation	
						YES	NO
	B1					<input type="checkbox"/>	<input type="checkbox"/>
	B2					<input type="checkbox"/>	<input type="checkbox"/>
	B3					<input type="checkbox"/>	<input type="checkbox"/>
	B4					<input checked="" type="checkbox"/>	<input checked="" type="checkbox"/>
	B5					<input type="checkbox"/>	<input type="checkbox"/>

## OTHER ART

*Examiner Initial	Including Author, Title, Date, Pertinent Pages, Etc.	
AS	C1	Yue, et al., "Plasma etching endpoint detection using multiple wavelengths for small open-area wafers," J. Vac. Sci. Technol. A, 19(1), Jan/Feb 2001, 66-75
	C2	
	C3	

Examiner Andie C. Lawrence Date Considered 07-08-05

\*EXAMINER: Initial if reference considered, whether or not citation is in conformance with MPEP 609; Draw line through citation if not in conformance and not considered. Include copy of this form with your communication to applicant.